

CATRENE: GIVER and TAKER for 3D Innovation

**SEMI's European 3D TSV Summit
January 22nd 2014
Grenoble**



- SPTS Technologies designs, manufactures, sells, and supports etch, PVD, CVD and thermal capital equipment, providing advanced wafer processing technologies for the microelectronics industry.
- Formed in 2009, SPTS brings together over 40 years wafer processing experience from companies including Watkins-Johnson, Trikon Technologies, STS, Aviza Technology and AMMS.
- The solutions offered by SPTS include market-leading silicon etch, dielectric etch, dry-release etch, PVD, PECVD, APCVD and large batch vertical furnaces
- SPTS Technologies sas (France) is a subsidiary of SPTS technologies dedicated for sales, support & service, R&D.



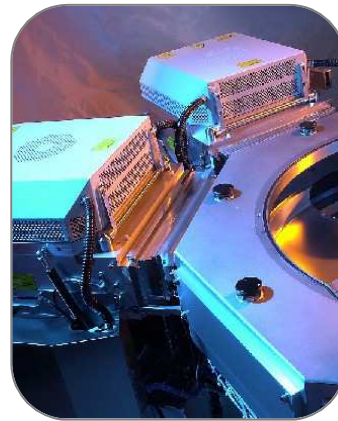
- Broad supplier of wafer processing solutions
 - For MEMS, compound semi, power and packaging markets
- Formed in Oct-09 via merger of former STS and Aviza
 - MBO in Jun-11
- Manufacturing sites in UK and US
 - Global presence with 35 worldwide locations



Etch



PVD



CVD

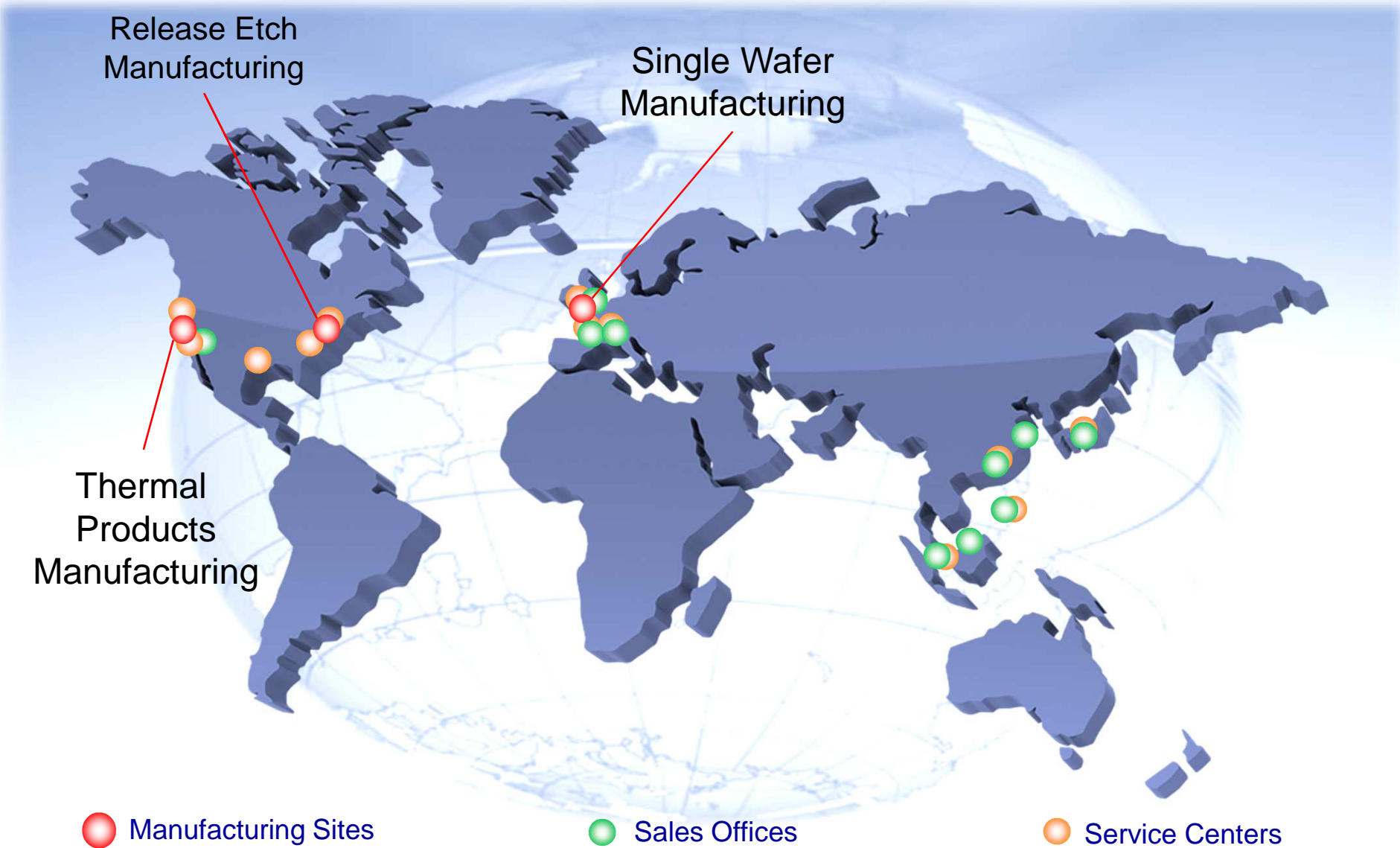


Thermal



Release Etch

SPTS - Global Presence



SPTS Equipment is Used for Making...



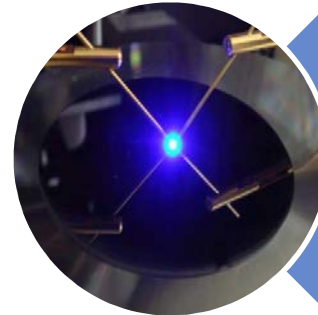
MEMS

- Micro Electro Mechanical Systems in inkjet heads, smart-phones, games consoles, and tablets



LEDs

- LED-backlit TVs, general indication, and automotive / industrial / domestic lighting



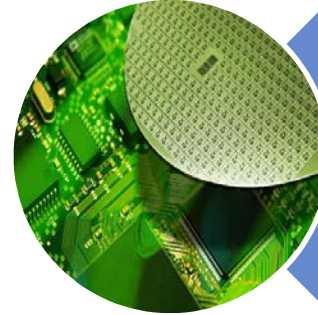
Power Devices

- Control / reduce / generate power used in electronic and power systems



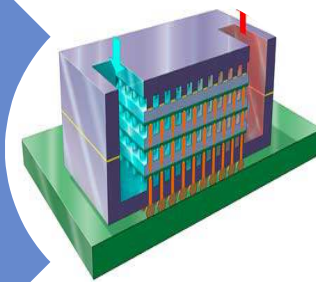
Semiconductor Devices

- Mainstream Si-based devices, including front-end CMOS/Logic/DRAM processing



Advanced Packaging

- Packaging semiconductor devices to reduce size and increase performance

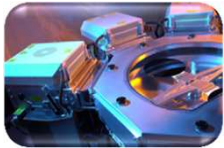
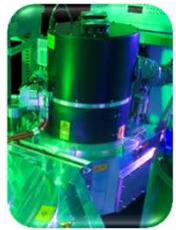


High Speed Electronics

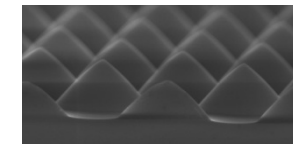
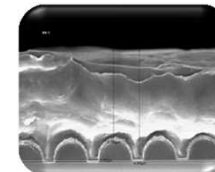
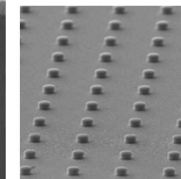
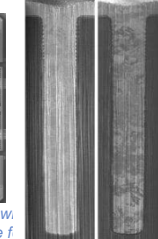
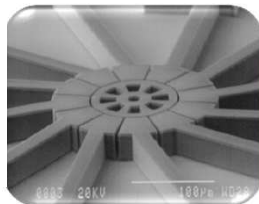
- Electronic devices using III-V materials to increase the speed /performance in devices



SPTS Solutions



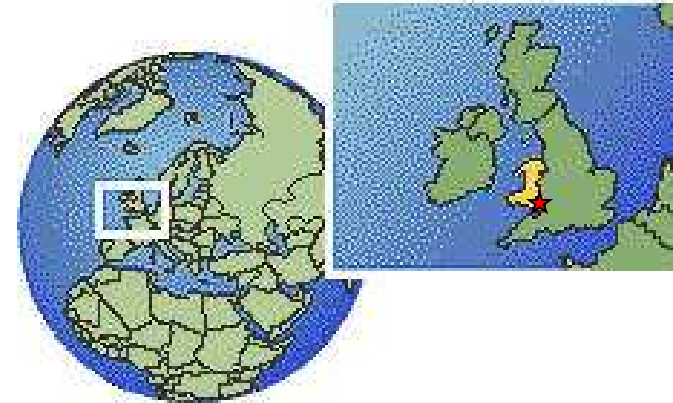
| Products | MEMS | Adv Packaging | Power | Compound |
|--|--|--|---|--|
| Etch Omega | Deep Si Deep oxide | TSV Oxide liner Via reveal | Active trenches Deeper trenches SiC, GaN | Backside Vias Dielectrics SiC, GaN Sapphire |
| CVD Delta | Low stress SiN Low temp for TSV High RI etch mask | Low temp TSV liners Via reveal SiN, SiO Tuned stack stress | | MIMCAP SiN Ammonia free SiN Dense SiN passivation |
| PVD Sigma | Piezo AlN Bolometer Resistors Low Stress Al Motion Sensor Electrodes | UBM/RDL TSV Cu Barrier/Seed Si & Mold Wafers | Thick Al, Cu W-Plug Liner/Barrier Thin Wafer BSM SiC, GaN | Backside Via TFR SAW SiOx BAW AlN |
| Release division Primaxx-vapor HF Xactix-vapor XeF2 | Dry oxide release/ Dry silicon release | | | |
| Thermal AVP/RVP | Low stress SiN Thick poly-Si Low temp SiGe | FO-WLP anneals Tox/LPCVD liners Cu anneal | Drive-in anneal Tox/LPCVD liners Poly-Si trench fill | Low temp anneal |



Single Wafer Products Division



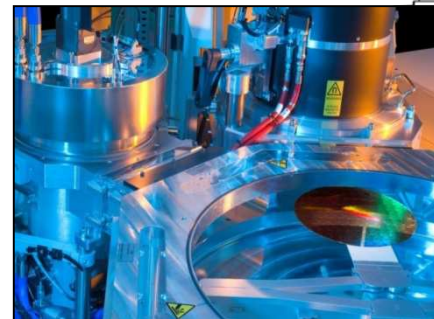
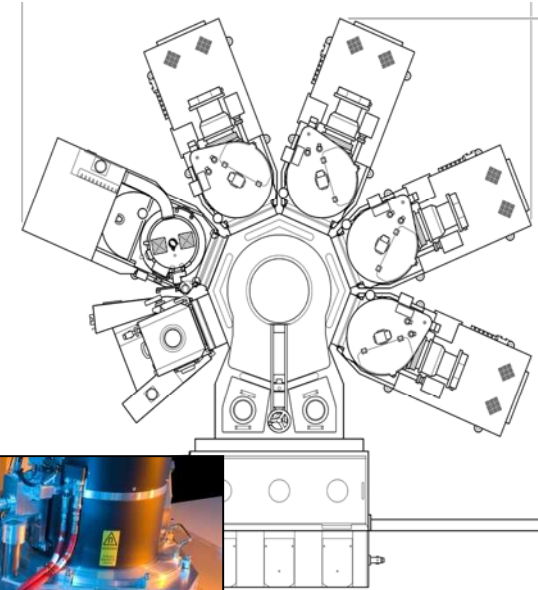
- Location
 - Newport, South Wales, UK
- 104,200 sq ft
- 22 Universal Test Cells
- 15 Universal Assembly Cells
- 5S-Controlled Class 1000 cleanroom environment
- Flexible, multi-skilled workforce
- Lean culture with value-stream mapping
- Practice Design-for-manufacturing (DFM)



SPTS Product Strategy in 3D



- Started with WLCSP in 2005
 - 1st generation TSV, for CMOS image sensors
 - Now used for fingerprint sensors
 - Still highest volume TSV device
- Offering for 2.5 and 3D stacking
 - Etch: Via etch and via reveal
 - DCVD: Via isolation & via reveal
 - PVD: TSV metals & bump/RDL
- Product strategy
 - High productivity, low CoO.
 - Film stability at low temp
- Running on...
 - Single technology systems
 - Or multi-tech on one platform

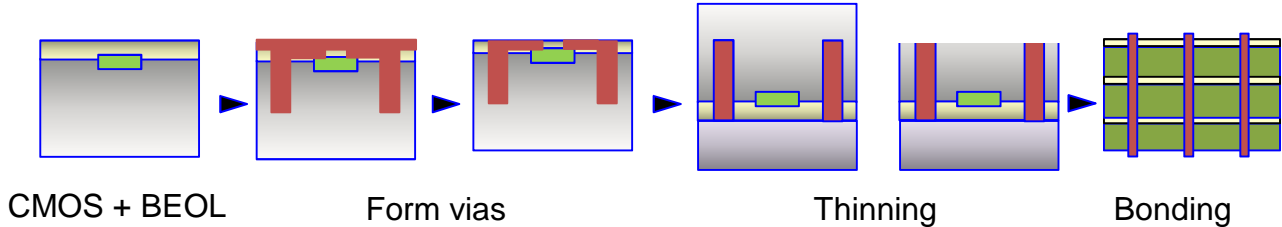


Versalis fxP
PVD, etch and CVD on one platform
Ideal for R&D, pilot
Saves capex \$\$ & floorspace

Projects contribution

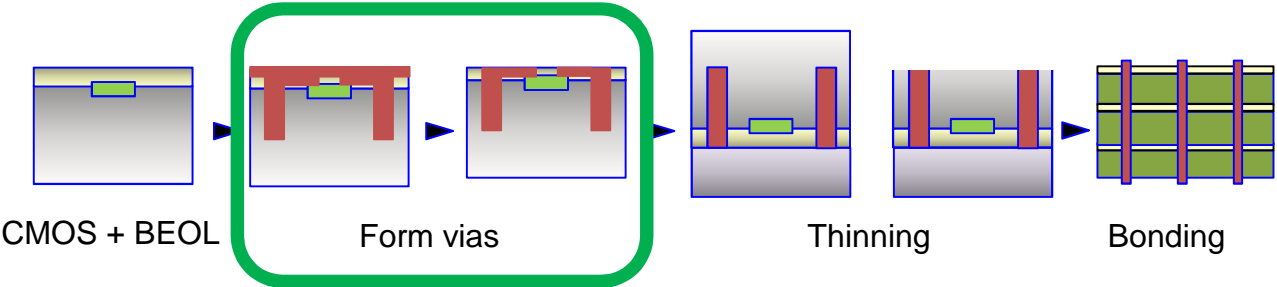


- 3D process flow

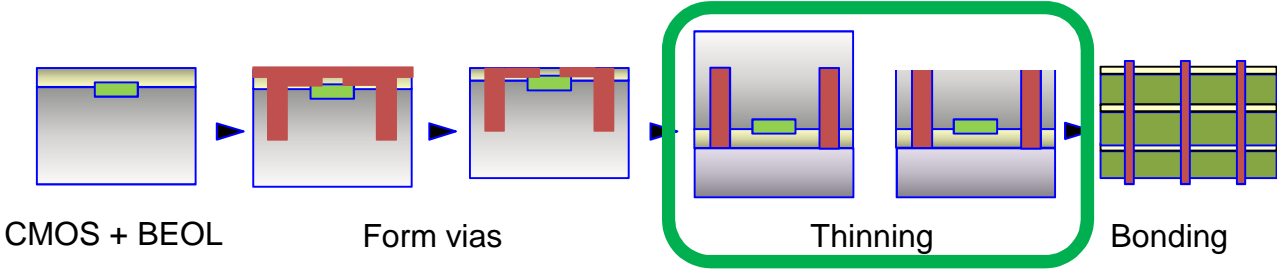


- SPTS contribution

 - Vias : Etch, Deposition (insulation, Metal : barrier, seed)



 - Vias reveal

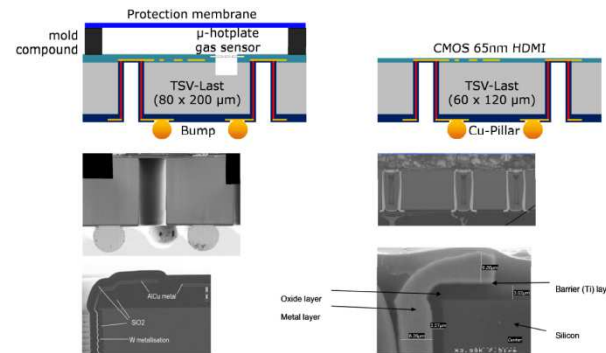


Projects contribution

■ CATRENE Projects

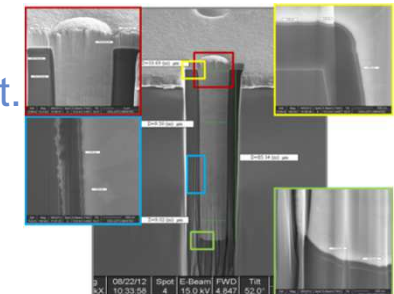
■ COCOA

- 3D integration technology platform covering all processes required from vertical interconnects and robust bonding to innovative packaging to address new 3D products (6:1 & 20:1 A.R Vias).
- Realization of product demonstrators for multimedia and wireless applications and sensor integration applications.



■ Master 3D

- 3D ICs with Through Silicon Vias (TSV) and Wafer Level Packaging (WLP).
- **Tool enhancements to support high yield, mass production**
- Functional and Final Test concepts
- Characterization and in-line Metrology methods development.



- Direct discussion between all partners from R&D lab to end users
- Collaboration with labs :
 - Validate concept & feasibility of advanced recipes & hardware
- Collaboration with end users
 - Define precisely process perf. specification
 - Aim to demonstrate the robustness and stability of processes & tools
- Collaboration with other equipment Vendors
 - Understand complete process flow specifications & limitations

Why to chose CATRENE?



- Catrene offers to grant one part of the strategic R&D and product development
- Catrene offers an easy & free way of communication with all 3D actors from equipment vendors to IDMs
- Catrene offers us the possibility to demonstrate our tools & process capabilities for new technologies for IDMs on full demonstrators